Functional Polymer films deposited in vapor phase for nanotechnology

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A new polymer deposition method, the initiated chemical vapor deposition (iCVD), was utilized for fabrication of novel thin film materials and structures. The iCVD is a process that can deposit functional polymer films with the exceptional compositional control and conformality. The solvent-free process provides non-toxic coatings of anti-microbial, superhydrophobic, functionalizable, insulating, and bio-compatible polymers without damaging underlying substrates. With this versatile tool, we are exploiting the possibility of the functional polymer coatings to develop next-generation of engineering devices. In this presentation, we are focusing on the application of functional polymer coatings to the application to nanotechnology.